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TRANSMITTAL FORM			Filing Date 08/24/2002					
			First Named Inventor Johan-Valentin Kahi					
			Art Unit 1753					
			Examiner Name Barton, Jeffrey Thomas			frey Thomas		
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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application No. Filing Date		First Named Inventor	Atty. Docket No.	Confirmation No.
10/049,245	10/049,245 06/24/2002 Joha		GRUNP18	9295
		• • •		
	Invention		Examiner	Art Unit
Method and D	evice for the Elect	rophoretic Separation of	Parton Jeffrey Thoma	e 1753

AMENDMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Particles, Especially of Macromolecules

Sir:

In response to the Examiner's Action mailed October 1, 2004, please amend the application as follows:

Application No. 10/049,245
Amendment

Page 2

Amendments to the Written Description

Please amend the written description as follows:

The paragraph on page 1, beginning at line 4:

The present invention relates to a method and an apparatus for separating particles, in particular, macromolecules, such as DNA, RNA macromolecules, DNA, RNA oliogomere oligomers and proteins by electrophoresis.

The paragraph on page 11, beginning at line 19:

In the following a first embodiment of the method for the electrophoretic separation of marcomolecules macromolecules is described with reference to Figure 1.

The paragraph beginning on page 13 at line 25:

In the embodiments of Figure 3 a substrate is used the ribs of which exhibit a periodicity in the range of 2 nm to 200 nm. The height of the ribs thereby ranges from 0.1 nm to 10 nm. In a substrate comprising the above indicated plastics, the structuring can be formed by, for example, imprinting a dye die containing the negative of the desired form. To this end, the plastic is preferably heated. A silicon wafer cut in the (111) plane and etched with KOH may be used as the dye die.

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